

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1606669	Semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/10 13:34
S2	904959	S1 not (@rlad>"20040319" @ad>"20040319")	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2006/01/10 13:36
S3	2812	S2 and (porous porosity pore) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/10 13:37
S4	123	S3 and (oxygen ozone o2 o3 "o.sub.2" "o.sub.3") with plasma with (hydrogen ammonia h2 "h.sub.2" nh3 "nh.sub.3" reduc\$4) same (organic polymer\$2 resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/10 13:43
S5	96	S4 and (oxygen ozone o2 o3 "o.sub.2" "o.sub.3") with plasma with (hydrogen ammonia h2 "h.sub.2" nh3 "nh.sub.3" reduc\$4) with (organic polymer\$2 resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/10 13:44
S6	96	S5 and (oxygen ozone o2 o3 "o.sub.2" "o.sub.3") with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/10 13:44